

Title (en)  
SILVER BASED PHOTOMASKS

Title (de)  
AUF SILBER BASIERENDE PHOTOMASKEN

Title (fr)  
PHOTOMASQUES A BASE D'ARGENT

Publication  
**EP 1092173 A1 20010418 (EN)**

Application  
**EP 99923736 A 19990528**

Priority  
• GB 9901484 W 19990528  
• GB 9811563 A 19980530

Abstract (en)  
[origin: WO9963406A1] In the field of semiconductor photomask manufacture there is a need to produce photomasks more rapidly and with fewer flaws. There is also a need for photomasks capable of producing much finer resolution circuits than hitherto. There is disclosed a method of manufacturing a photomask (10) in which a substrate (11) is coated with an emulsion of gelatin (18) and a photosensitive silver halide (17). On exposure to an electron beam (15) or a laser beam, controlled to generate a desired pattern of movement, the silver halide reduces to create a photomask (10) after development and fixing.

IPC 1-7  
**G03F 1/12**

IPC 8 full level  
**G03F 1/54** (2012.01); **H01L 21/027** (2006.01)

CPC (source: EP)  
**G03F 1/54** (2013.01)

Citation (search report)  
See references of WO 9963406A1

Designated contracting state (EPC)  
DE FR GB IT NL SE

DOCDB simple family (publication)  
**WO 9963406 A1 19991209**; AU 4050199 A 19991220; EP 1092173 A1 20010418; GB 9811563 D0 19980729; JP 2002517785 A 20020618

DOCDB simple family (application)  
**GB 9901484 W 19990528**; AU 4050199 A 19990528; EP 99923736 A 19990528; GB 9811563 A 19980530; JP 2000552555 A 19990528